



Netscape

> <u>Play Games</u> > Auctions

> Auctions > CreditReport

> Free Web Site



Nanotechnology

with Steve Lenhert Your Guide to One of Over 700 Sites

Home Articles Forums Chat Contact Guide Newsletter

Search

Subjects

Introduction
Education
Research
Methods
Publications
Discussion

Industry
Computing
Modeling
Jobs
Implications
News

SPM SEM Nanolithography Self-Assembly Components Images

MEMS NEMS Quantum Biology History People Terminology

Subject Library

All articles on this topic

Related Sites

from About

- Artificial Intelligence
- · Biology
- · Biotech/Biomedical
- Chemical Engineering
- Chemistry
- Composite Materials
- · <u>Inventors</u>
- Silicon Valley, CASpace/Astronomy
- Space/Astronomy

About Also Recommends
Apply to become

a partner for this site.

Quantum Interferometry

Dateline: 10/11/2000

One of the primary driving forces behind the development of nanotechnology is the demand for smaller computer chips. The primary method used for chip fabrication is optical lithography. This method runs into a physical limit at the nanoscale because of a barrier known as the far-field diffraction limit. However, this limit was placed on light by physicists in classical times, before the development of quantum mechanics. The quantum mechanical model of light says that when two photons are entangled, they effectively have half of the wavelength that they have when they are not entangled. If three or more photons are entangled the effective wavelength is even smaller. Physicists are finding new ways to entangle photons (and other objects), for instance by passing them through special crystals. Quantum interferometric lithography exploits this property to focus light beyond half of its wavelength for patterning surfaces such as a silicon chip [1]. This may be good news for chip manufacturers who might be able to add entanglement crystals to their lithography machinery and continue to make a lot of money by selling nanochips.

Return to the Newsletter

Subscribe to the Nanotechnology Newsletter

Name Email

Reference:

[1] A. N. Boto, P. Kok, D. S. Abrams, S. L. Braunstein, C. P. Williams, J. P. Dowling, "Quantum Interferometric Optical Lithography: Exploiting Entanglement to Beat the Diffraction Limit," (02 October **2000**) *Physical Review Letters* 85. Abstract

Advertising



